

10/716,702



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Substitute Specification

Application No. 10/716,702

TITLE OF THE INVENTION

STAGE APPARATUS AND METHOD OF CONTROLLING THE SAME

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FIELD OF THE INVENTION

[0001] The present invention relates to a movable stage apparatus and a method of controlling the same. More particularly, the present invention relates to a movable stage apparatus suitable for a wafer stage, or the like, in an exposure apparatus, and a method of controlling the same.

BACKGROUND OF THE INVENTION

[0002] As the accuracy of an exposure apparatus increases, a movable stage apparatus loaded with a six-axis fine movement stage as a wafer stage has been employed. A stage apparatus of this type is disclosed in, e.g., Japanese Patent Laid Open No. 2000-106344. A general stage apparatus will be described below with reference to Figs. 15 to 18.

[0003] Fig. 15 is a view schematically showing a general movement stage apparatus. A yaw guide 301 is formed on a stage surface plate 300, and a Y slider 302 guided by the yaw guide 301 and the stage surface plate 300 is formed. Air pads (not shown) are provided between the Y slider 302 and stage surface plate 300, and between the Y slider 302 and yaw guide 301. Accordingly, the Y slider 302 can slide in the Y direction.